**AMENDMENTS TO THE CLAIMS:**

*This listing of claims will replace all prior versions, and listings, of claims in the application:*

1. (Canceled)

2. (Currently amended) A method for fabricating a substrate with a parallax barrier layer, the method comprising:

(a) preparing a first substrate, which has a first principal surface and a second principal surface that are opposed to each other and which is made of a transparent material;

(b) providing a parallax barrier layer with a predetermined pattern on the first principal surface of the first substrate;

(c) forming a first layer, which satisfies a prescribed positional relationship with the parallax barrier layer, on the second principal surface of the first substrate; and

~~The method of claim 1,~~ wherein the step (b) includes a step of making a first alignment mark.

3. (original) The method of claim 2, wherein the step (c) includes a step of locating the first alignment mark through the first substrate and achieving alignment with respect to the first alignment mark.

4. (Previously presented) The method of claim 2, wherein the first alignment mark is made of a material of the parallax barrier layer.

5. (Currently amended) The method of claim [[1]] 2, wherein the parallax barrier layer is made of a metallic material.

6. (Currently amended) The method of claim [[1]] 2, wherein the step (c) includes a step of forming a color filter layer as the first layer.

7. (Currently amended) The method of claim [[1]] 2, wherein the step (c) includes a step of forming a black matrix layer as the first layer.

8. (Currently amended) A method for fabricating a substrate with a parallax barrier layer, the method comprising:

(a) preparing a first substrate, which has a first principal surface and a second principal surface that are opposed to each other and which is made of a transparent material;

(b) providing a parallax barrier layer with a predetermined pattern on the first principal surface of the first substrate;

(c) forming a first layer, which satisfies a prescribed positional relationship with the parallax barrier layer, on the second principal surface of the first substrate; and

~~The method of claim 1,~~ wherein the step (c) further includes a step of making an ~~second~~ alignment mark of a material of the first layer.

9. (Currently amended) A method for fabricating a display device, the method comprising steps of:

(A) preparing a substrate with a parallax barrier layer by the method of claim [[1]] 2;

(B) securing a second substrate to the substrate with the parallax barrier layer with a predetermined gap provided between the two substrates; and

(C) forming a display medium layer between the substrate with the parallax barrier layer and the second substrate.

10. (original) The method of claim 9, further comprising a step of (D) dividing a panel, in which the substrate with the parallax barrier layer and the second substrate are combined with each other, into a number of smaller panels after one of the steps (B) and (C).

11. (Previously presented) The method of claim 9, wherein the display medium layer is a liquid crystal layer.

12. (original) The method of claim 11, further comprising a step of arranging a polarizer on a viewer-side surface of the parallax barrier layer after the step (D).

13-15. (Canceled)

16. (New) A method for fabricating a substrate with a parallax barrier layer, the method comprising steps of:

(a) preparing a first substrate, which has a first principal surface and a second principal surface that are opposed to each other and which is made of a transparent material;

(b) providing a parallax barrier layer with a predetermined pattern on the first principal surface of the first substrate;

(c) forming a first layer, which satisfies a prescribed positional relationship with the parallax barrier layer, on the second principal surface of the first substrate; and

(d) forming a second layer, which satisfies a prescribed positional relationship with the first layer, on the second principal surface of the first substrate.

17. (New) The method of claim 16, wherein the step (b) includes a step of making a first alignment mark.

18. (New) The method of claim 17, wherein the step (c) further includes a step of making a second alignment mark of a material of the first layer.

19. (New) The method of claim 18, wherein the step (c) further includes a step of locating the first alignment mark through the first substrate achieving alignment with respect to the first alignment mark, and

wherein the step (d) further includes a step of locating the second alignment mark and achieving alignment with respect to the second alignment mark.

20. (New) The method of claim 17, wherein the first alignment mark is made of a material of the parallax barrier layer.

21. (New) The method of claim 16, wherein the parallax barrier layer comprises metallic material.

22. (New) The method of claim 16, wherein the step (c) includes a step of forming a first color layer of a color filter as the first layer, and

wherein the step (d) includes a step of forming a second color layer of the color filter as the second layer.

23. (New) The method of claim 16, wherein the step (c) includes a step of forming a black matrix layer as the first layer, and

wherein the step (d) includes a step of forming a first color layer of a color filter as the second layer.

24. (New) The method of claim 22, further comprising a step of (e) forming a third layer, which satisfies a prescribed positional relationship with the first and second layers, on the second principal surface of the first substrate.

25. (New) The method of claim 24, wherein the step (e) further includes a step of locating the second alignment mark and achieving alignment with respect to the second alignment mark.

26. (New) The method of claim 24, wherein the step (e) includes a step of forming a third color layer of the color filter as the third layer.

27. (New) The method of claim 26, further comprising a step of (f) forming a black matrix layer, which satisfies a prescribed positional relationship with the first, second and third layers, on the second principal surface of the first substrate.

28. (New) The method of claim 23, further comprising a step of (e) forming second and third color layers, which satisfies a prescribed positional relationship with the black matrix layer and the first color layer, on the second principal surface of the first substrate.

29. (New) The method of claim 28, wherein the step (e) further includes a step of locating the second alignment mark and achieving alignment with respect to the second alignment mark.

30. (New) A method of fabricating a substrate with a parallax barrier layer, the method comprising steps of:

(a) preparing a first substrate, which has a first principal surface and a second principal surface that are opposed to each other and which is made of a transparent material;

(b) providing a parallax barrier layer with a predetermined pattern on the first principal surface of the first substrate;

(c) forming a first layer, which satisfies a prescribed positional relationship with the parallax barrier layer, on the second principal surface of the first substrate, and making an alignment mark, which is used for achieving alignment in forming a second layer which has a prescribed positional relationship with the first layer.